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X-Ray And Particle Microscopy Using Fresnel-Zone Plates

Natale A. Coglio

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ANALYTICAL ELECTRON MICROSCOPY USING FRESNEL-ZONE PLATES¹

R. W. Coglio

Department of Physics, University of California, Berkeley, California 94720
Lawrence Livermore National Laboratory, Livermore, California 94550
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Fresnel zone plates are being used for x-ray microcopy covering a broad spectral range (100 eV - 100 keV). They are being used as (1) the focusing element for microcopy (100 eV - 10 keV), "soft" x-ray (100 eV - 10 keV) spectroscopy and (2) spectroscopy (on a channel imaging mode) for soft x-ray resolution (100 eV), "hard" x-ray (10 keV) imaging applications.

THE FRESNEL ZONE PLATE AS HIGH RESOLUTION X-RAY LENS FOR MICROSCOPY

A Fresnel zone plate may be viewed as a circular diffractive x-ray transmission grating with alternately transparent and opaque zones of equal area. As such it is a diffraction limited focusing (imaging) element providing a focal spot diameter (resolution) approaching the physical feature size (outermost zone width) of the zone plate structure.² Significant advances in microfabrication techniques have allowed the fabrication of aberration free zone plate patterns having linewidths as small as $\lambda/60$ with the real possibility of extending this capability to even narrower linewidth, higher resolution structures.³ A free standing silicon Fresnel zone plate structure fabricated using scanning electron beam lithographic techniques is shown in Fig. 1. Such structures are fabricated at LLNL, Livermore Laboratory, and being tested and used as x-ray focusing elements in experiments at Lawrence Livermore National Laboratory. Fig. 2 shows x-ray imaging test results from an experiment in which the zone plate focusing element was used to image a resolution test pattern backlit with K_{α} radiation ($\lambda = 0.175 \text{ \AA}$). The resolution test pattern was in this case a "crude" zone plate having 2.0 μm minimum zone width. The results show the 1.0 μm lines and spaces clearly resolved, although the

data suffers from shot noise due to x-ray source intensity limitations.

Fig. 1. Image of a single period of a grating. Modulation of the intensity is indicated by the vertical scale bar on the right.

Fig. 2. Profile of a single period of a grating. The vertical scale bar indicates intensity.

Additional resolution test patterns are being constructed using test patterns having sub-micron features sizes.

FRESNEL ZONE PLATE AS GLOW DISCHARGE SOURCE FOR X-RAY IMAGING

Fresnel zone plates used as diffractive x-ray lens are the more appealing and interesting for "soft" (0.1-10 keV) x-ray applications. At x-ray energies there is a low x-ray flux transmission through the metal zones, and reduced diffractive

This technique is currently being used to image high energy x-ray⁶ and particle⁷ emissions from laser fusion targets at Lawrence Livermore National Laboratory. Such an image of suprathermal x-ray emission (20-25 keV) from a laser imploded microballon target is shown in Fig. 3 and discussed in Ref. 4).

Fig. 4. Separation of x-ray emission (10-15 keV) from a laser fusion target using the collimating effect of a thin, non-flat, metal foil placed between the target and the detector (10-50 μ m).

Continued advances in microfabrication technology allowing the production of x-ray emitting elements having widths on the order of (1-100 μ m) and cross-sectional lengths of the order of (100 μ m) will extend x-ray microscopy into an unexplored parameter region (resolution $\sim 10^{-3}$ λ , x-ray energy $\sim 10^3$ eV).

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FIG. 1

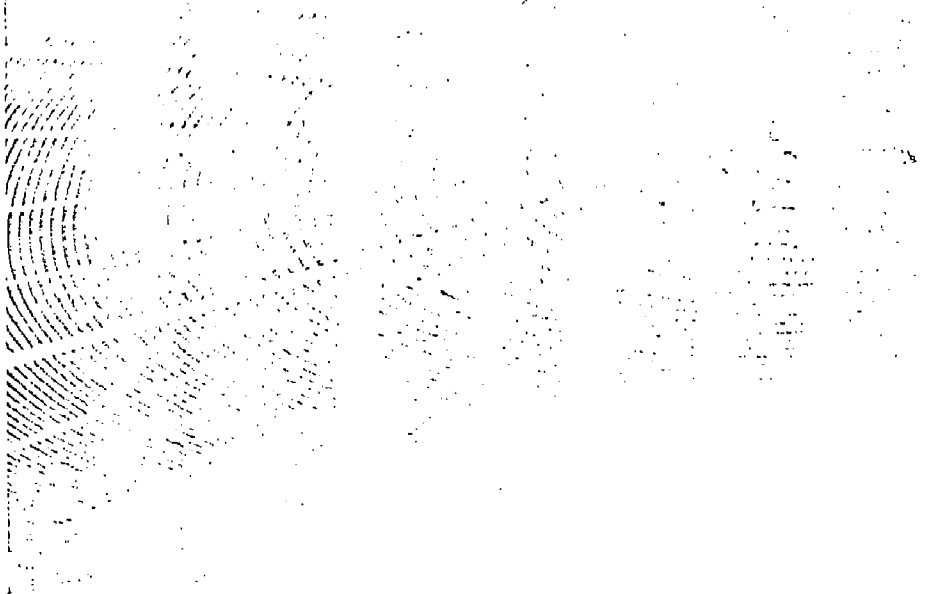


Fig 2

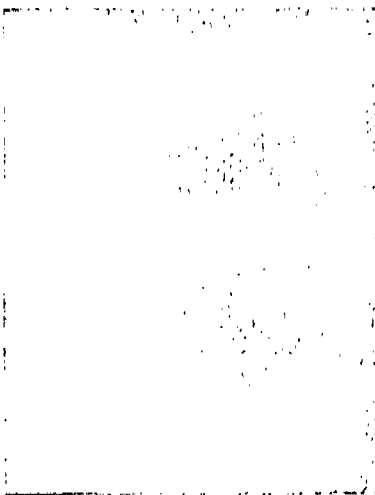
Initial results



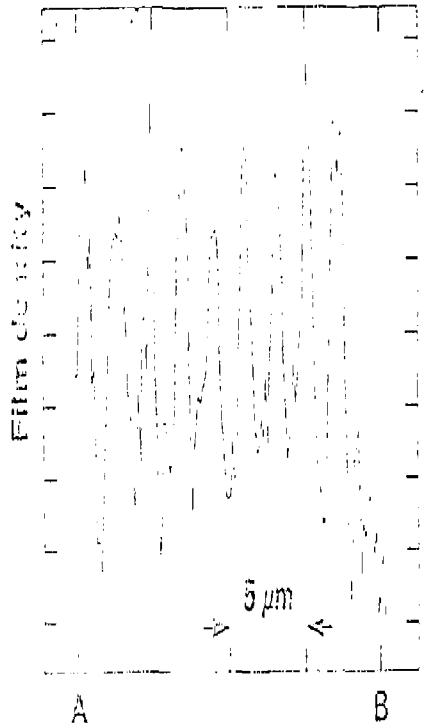
Test pattern
1.0 μm lines



X-ray "lens" image



X-ray "lens" image

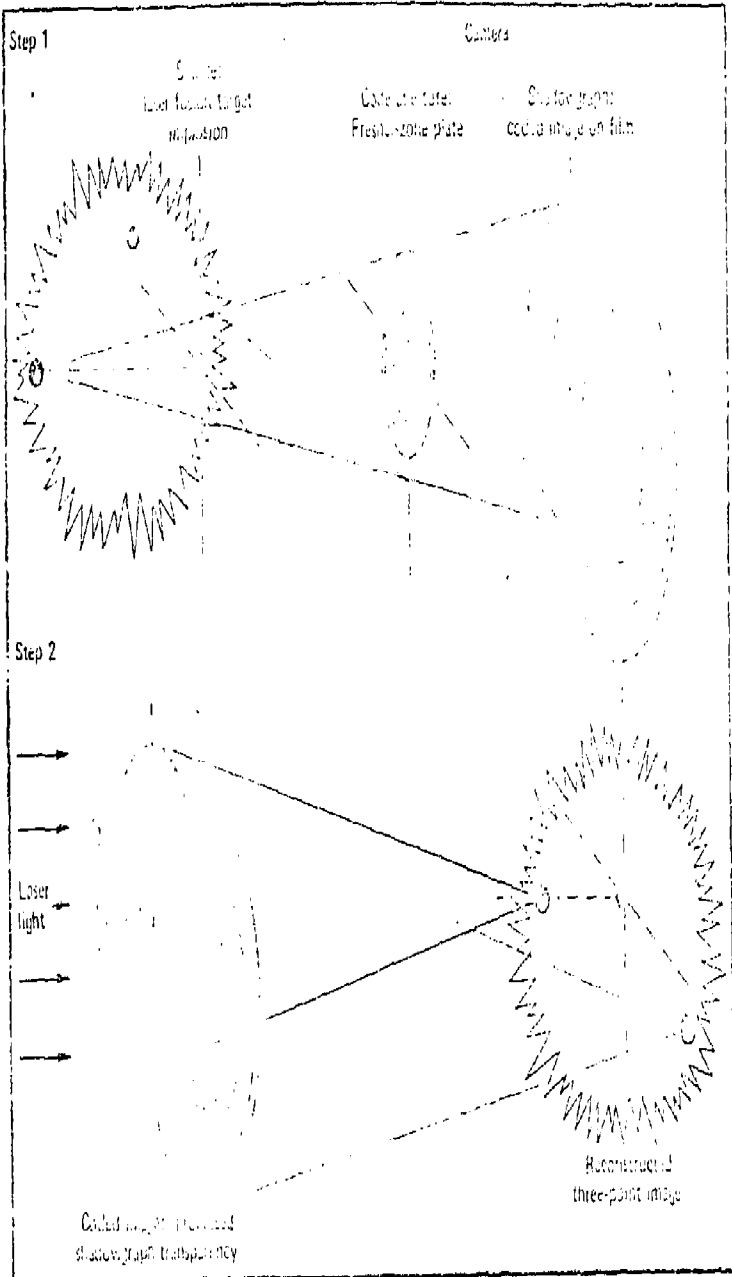


Conclude:

• 1.0 μm lines and spaces are clearly resolved

ZONE PLATE CODED IMAGING: PRINCIPLES

Fig 3



40 90 0578-1795



Fig 4